

24. (Amended) A control system which corrects the measurement results of the first and second measurement systems on the basis of the measurement results of the first and second measurement systems.

32. (Amended) An exposure apparatus provided with the stage device according to claim 1, wherein masks on which mutually different patterns are formed are placed on the plurality of movable stages of the stage device, and the patterns of the masks on the plurality of movable stages are alternately transferred onto a substrate while being positioned.

43. (Amended) An exposure apparatus provided with the stage device according to claim 1, wherein a mask is placed on a first movable stage among the plurality of movable stages of the stage device, a characteristic measurement apparatus which measures characteristics in transfer of a pattern of the mask is placed on a second movable stage of the plurality of movable stages, and the pattern of the mask is transferred onto a substrate.

6. (Amended) An exposure apparatus provided with the stage device according to claim 1, wherein a substrate is placed on each of the plurality of movable stages of the stage device, and the plurality of substrates are alternately exposed with mask patterns while the plurality of movable stages are alternately positioned at an exposure position.

46. (Amended) An exposure apparatus provided with the stage device according to claim 1 and a projection optical system,

wherein a substrate is placed on a first movable stage of the plurality of movable stages of the stage device, a characteristic measurement apparatus which measures imaging characteristics of the projection optical system is placed on a second movable stage of the plurality of movable stages, and the substrate on the first movable stage is exposed with a mask pattern via the projection optical system.

108. (Amended) A positioning method that makes use of the stage device according to claim 1, wherein when one of the plurality of movable stages enters the measurement range of the first measurement system, the amount of positional deviation of the

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one movable stage from the reference position within the measurement range, or the degree of coincidence of the one movable stage with respect to the reference position, is measured by the second measurement system, and a measurement value obtained with the first measurement system is corrected on the basis of a measurement result of the second measurement system.

*14/11* (Amended) An exposure apparatus provided with the stage device according to claim ~~2~~, wherein masks on which mutually different patterns are formed are placed on the plurality of movable stages of the stage device, and the patterns of the masks on the plurality of movable stages are alternately transferred onto a substrate while being positioned.

*B3 16/11* (Amended) An exposure apparatus provided with the stage device according to claim ~~2~~, wherein a mask is placed on a first movable stage among the plurality of movable stages of the stage device, a characteristic measurement apparatus which measures characteristics in transfer of a pattern of the mask is placed on a second movable stage of the plurality of movable stages, and the pattern of the mask is transferred onto a substrate.

*18/19* (Amended) An exposure apparatus provided with the stage device according to claim ~~2~~, wherein a substrate is placed on each of the plurality of movable stages of the stage device, and the plurality of substrates are alternately exposed with mask patterns while the plurality of movable stages are alternately positioned at an exposure position.

*21/20* (Amended) An exposure apparatus provided with the stage device according to claim ~~2~~ and a projection optical system,

wherein a substrate is placed on a first movable stage of the plurality of movable stages of the stage device, a characteristic measurement apparatus which measures imaging characteristics of the projection optical system is placed on a second movable stage of the plurality of movable stages, and the substrate on the first movable stage is exposed with a mask pattern via the projection optical system.